ABSTRACT

METHOD FOR FORMING INSULATING FILM

[Problem] To provide a method capable of forming an insulating film having homogeneous and high bulk density and less suffering defects.

[Means for solving] A substrate surface is coated with a silicon dioxide dispersion containing silicon dioxide fine particles, a polymer, a surfactant and a dispersion medium; and then further coated with a polysilazane composition; and thereafter heated to form an insulating film.

Nil